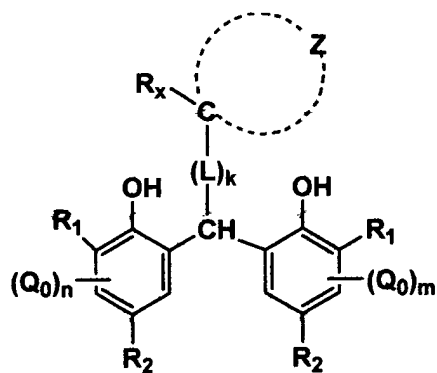# CLAIM AMENDMENTS

Claim 1 (Currently Amended)

A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver salt, a first reducing agent and a second reducing agent,

wherein when a regression line is obtained by plotting color coordinates (u*, v*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0, 1.5 and the minimum density on a two dimensional coordinates of CIE 1976 (L* u* v*) color space, in which the abscissa is u* and the ordinate is v*,

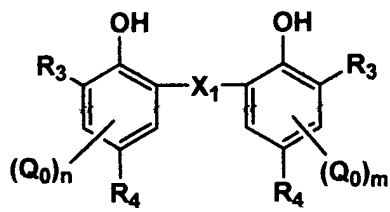a coefficient of determination R^2 of the regression line is from 0.998 to 1.000

wherein said first reducing agent is represented by following Formula (A-1), said second reducing agent is a represented by following Formula (A-3), and said light-sensitive material further comprises a compound represented by following Formula (A-4),
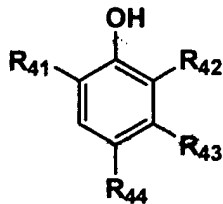
Formula (A-1)

wherein Z is a group of atoms necessary for forming a 3-through 10-membered ring together with the carbon atom; R_x is a hydrogen atom, an alkyl group, an alkenyl group or alkynyl group; R_1, R_2 and Q_0 are each a group capable of substituting on the benzene ring; L is divalent linking group; k is an integer of 0 or 1; and n and m are each an integer of 0 through 2; plural R_1, R_2 and Q_0 each may be the same or different,

Formula (A-3)

wherein X_1 is a chalcogen atom or -CH(R)-; R in -CH(R)- is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group or an alkynyl group; each R_3 is an alkyl group which may be the same or different and at least one of R_3 is a secondary or tertiary alkyl group; R_4 is a substituent; Q_0 is a substituent; and n and m are each an integer of 0 through 2,

3

Formula (A-4)

$$\text{OH} \quad R_{41}, R_{42}, R_{43}, R_{44}$$

wherein R_{41} is a substituted or unsubstituted alkyl group; R_{42} is a hydrogen atom, a substituted or unsubstituted alkyl group or a substituted or unsubstituted acylamino group provided that R_{41} and R_{42} are not a 2-hydroxyphenylmethyl group; R_{43} is a hydrogen atom of a substituted or unsubstituted alkyl group; and R_{44} is a substituent capable of substituting on the benzene ring.

Claim 2 (Original)

The thermally developable light-sensitive material of claim 1, wherein v^* value of the regression line is within a range of -5 to 5 when u^* is 0.

Claim 3 (Original)

The thermally developable light-sensitive material of claim 1, wherein the regression line has a gradient (u^* / v^*) of 0.7 to 2.5.
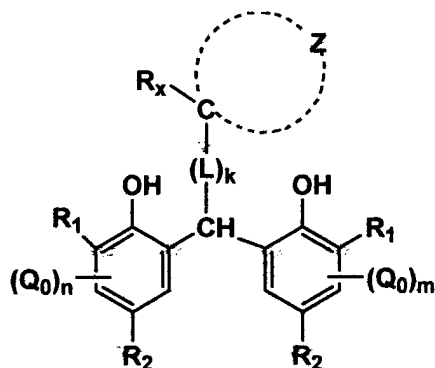
4

Claim 4 (Currently Amended)

A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver salt, a first reducing agent and a second reducing agent,

wherein when a regression line is obtained by plotting color coordinates (a*, b*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0, 1.5 and the minimum density on a two dimensional coordinates of CIE 1976 (L* a* b*) color space, in which the abscissa is a* and the ordinate is b*,

a coefficient of determination R^2 of the regression line is from 0.998 to 1.000
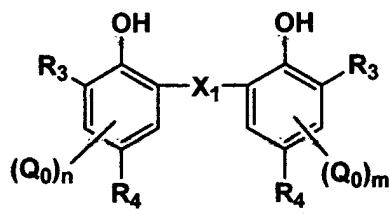
wherein said first reducing agent is represented by following Formula (A-1), said second reducing agent is a represented by following Formula (A-3), and said light-sensitive material further comprises a compound represented by following Formula (A-4),
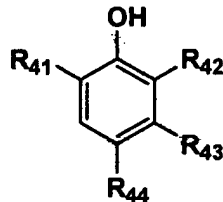
5

Formula (A-1)

wherein Z is a group of atoms necessary for forming a 3-through 10-membered ring together with the carbon atom; R_x is a hydrogen atom, an alkyl group, an alkenyl group or alkynyl group; R_1, R_2 and Q_0 are each a group capable of substituting on the benzene ring; L is divalent linking group; k is an integer of 0 or 1; and n and m are each an integer of 0 through 2; plural R_1, R_2 and Q_0 each may be the same or different,

Formula (A-3)

wherein X_1 is a chalcogen atom or -CH(R)-; R in -CH(R)- is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group or an alkynyl group; each R_3 is an alkyl group which may be the same or different and at least one of R_3 is a secondary or tertiary alkyl group; R_4 is a substituent; Q_0 is a substituent; and n and m are each an integer of 0 through 2,

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Formula (A-4)

$$\underset{R_{44}}{\overset{\displaystyle \overset{OH}{\underset{R_{41}}{\bigcirc}}R_{42}}{R_{43}}}$$

wherein R_{41} is a substituted or unsubstituted alkyl group; R_{42} is a hydrogen atom, a substituted or unsubstituted alkyl group or a substituted or unsubstituted acylamino group provided that R_{41} and R_{42} are not a 2-hydroxyphenylmethyl group; R_{43} is a hydrogen atom of a substituted or unsubstituted alkyl group; and R_{44} is a substituent capable of substituting on the benzene ring.

Claim 5 (Original)

The thermally developable light-sensitive material of claim 4, wherein b* value of the regression line is within a range of −5 to 5 when a* is 0.

Claim 6 (Original)

The thermally developable light-sensitive material of claim 4, wherein the regression line has a gradient (a* / b*) of 0.7 to 2.5.
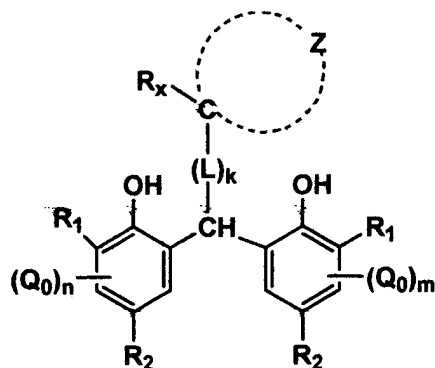
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Claim 7 (Currently Amended)

A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver salt, a first reducing agent and a second reducing agent,

wherein when a regression line is obtained by plotting color coordinates (u*, v*) of the thermally developable light-sensitive material at optical densities of 0.5, 1.0 and 1.5 on a two dimensional coordinates of CIE 1976 (L* u* v*) color space, in which the abscissa is u* and the ordinate is v*,

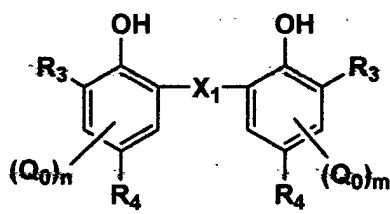a coefficient of determination R^2 of the regression line is from 0.998 to 1.000

wherein said first reducing agent is represented by following Formula (A-1), said second reducing agent is a represented by following Formula (A-3), and said light-sensitive material further comprises a compound represented by following Formula (A-4),
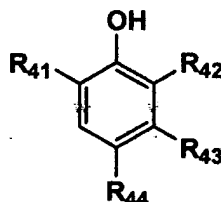
Formula (A-1)

8

wherein Z is a group of atoms necessary for forming a 3-through 10-membered ring together with the carbon atom; R_x is a hydrogen atom, an alkyl group, an alkenyl group or alkynyl group; R_1, R_2 and Q_0 are each a group capable of substituting on the benzene ring; L is divalent linking group; k is an integer of 0 or 1; and n and m are each an integer of 0 through 2; plural R_1, R_2 and Q_0 each may be the same or different,

Formula (A-3)

wherein X_1 is a chalcogen atom or $-CH(R)-$; R in $-CH(R)-$ is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group or an alkynyl group; each R_3 is an alkyl group which may be the same or different and at least one of R_3 is a secondary or tertiary alkyl group; R_4 is a substituent; Q_0 is a substituent; and n and m are each an integer of 0 through 2,

Formula (A-4)

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wherein R$_{41}$ is a substituted or unsubstituted alkyl group; R$_{42}$ is a hydrogen atom, a substituted or unsubstituted alkyl group or a substituted or unsubstituted acylamino group provided that R$_{41}$ and R$_{42}$ are not a 2-hydroxyphenylmethyl group; R$_{43}$ is a hydrogen atom of a substituted or unsubstituted alkyl group; and R$_{44}$ is a substituent capable of substituting on the benzene ring.

Claim 8 (Original)

The thermally developable light-sensitive material of claim 7, wherein v* value of the regression line is within a range of −5 to 5 when u* is 0.

Claim 9 (Original)

The thermally developable light-sensitive material of claim 7, wherein the regression line has a gradient (u* / v*) of 0.7 to 2.5.

Claim 10 (Currently Amended)

A thermally developable light-sensitive material comprising a support having thereon light-sensitive silver halide grains, an organic silver salt, a first reducing agent and a second reducing agent,
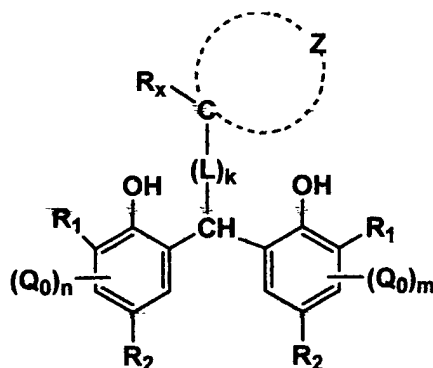
wherein when a regression line is obtained by plotting color coordinates (a*, b*) of the thermally developable light-

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sensitive material at optical densities of 0.5, 1.0 and 1.5 on a

two dimensional coordinates of CIE 1976 (L* a* b*) color space,

in which the abscissa is a* and the ordinate is b*,

a coefficient of determination R^2 of the regression line is

from 0.998 to 1.000
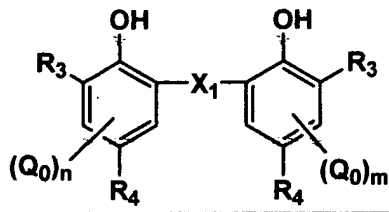
wherein said <u>first</u> reducing agent is represented by

following Formula (A-1), <u>said second reducing agent is a</u>

<u>represented by following Formula (A-3)</u>, and said light-sensitive

material further comprises a compound represented by following
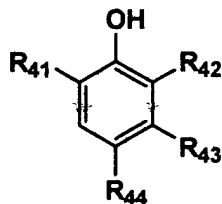
Formula (A-4),

Formula (A-1)

wherein Z is a group of atoms necessary for forming a 3-

through 10-membered ring together with the carbon atom; R_x is a

hydrogen atom, an alkyl group, an alkenyl group or alkynyl

group; R_1, R_2 and Q_0 are each a group capable of substituting on

the benzene ring; L is divalent linking group; k is an integer

of 0 or 1; and n and m are each an integer of 0 through 2;

plural R_1, R_2 and Q_0 each may be the same or different,

Formula (A-3)

wherein X_1 is a chalcogen atom or $-CH(R)-$; R in $-CH(R)-$ is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group or an alkynyl group; each R_3 is an alkyl group which may be the same or different and at least one of R_3 is a secondary or tertiary alkyl group; R_4 is a substituent; Q_0 is a substituent; and n and m are each an integer of 0 through 2,

Formula (A-4)

wherein R_{41} is a substituted or unsubstituted alkyl group; R_{42} is a hydrogen atom, a substituted or unsubstituted alkyl group or a substituted or unsubstituted acylamino group provided that R_{41} and R_{42} are not a 2-hydroxyphenylmethyl group; R_{43} is a hydrogen atom of a substituted or unsubstituted alkyl group; and R_{44} is a substituent capable of substituting on the benzene ring.

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Claim 11 (Original)

The thermally developable light-sensitive material of claim 10, wherein b* value of the regression line is within a range of -5 to 5 when a* is 0.

Claim 12 (Original)

The thermally developable light-sensitive material of claim 10, wherein the regression line has a gradient (a* / b*) of 0.7 to 2.5.

Claim 13 (Canceled)

Claim 14 (Previously Presented)

The thermally developable light-sensitive material of claim 1, wherein at least one of R_{41} and R_{42} is a divalent or trivalent alkyl group.

Claim 15 (Previously Presented)

The thermally developable light-sensitive material of claim 1, wherein the reducing agent represented by Formula (A-1) is a reducing agent represented by following Formula (A-2),

Formula (A-2)
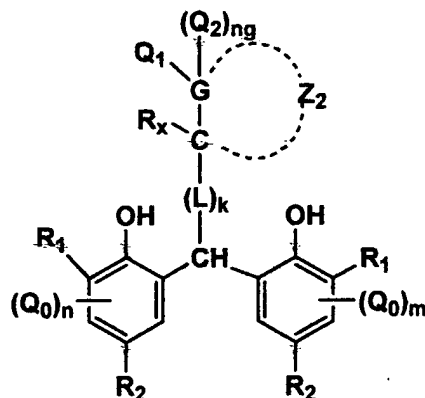
wherein Q_1 is a halogen atom, an alkyl group, an alkenyl group, an alkynyl group, an aryl group or a heterocyclic group; Q_2 is a hydrogen atom, a halogen atom, an alkyl group, an alkenyl group, an alkynyl group, an aryl group or a heterocyclic group; G is a nitrogen atom or a carbon atom that ng is 0 when G is the nitrogen atom and ng is 0 or 1 when the G is the oxygen atom; Z_2 is a group of atoms necessary for forming a 3- through 10-membered non-aromatic ring together with the carbon atom and G; and R_1, R_2, R_x, Q_0, L, k, n and m are each the same as those in Formula A-1.

Claim 16 (Original)

The thermally developable light-sensitive material of claim 15, wherein the non-aromatic ring formed by Z_2 together with the carbon atom and G in Formula (A-2) is a 6-member non-aromatic ring.

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Claim 17 (Original)

The thermally developable light-sensitive material of claim 1, wherein the thermally developable light-sensitive material further comprises a silver saving agent selected from the group consisting of vinyl compounds, hydrazine derivatives, silane compounds and tetravalent onium salt on the silver halide grain side of the support.

Claim 18 (Original)

An image forming method comprising the step of forming an image by developing the thermally developable light sensitive material described in claim 1 under a temperature of from 110 °C to 140 °C for a time of from 5 seconds to 20 seconds.

Claim 19 (Original)

An image forming method comprising the step of forming an image by exposing the thermally developable light-sensitive material described in claim 1 with a laser having an wavelength of from 400 nm to 830 nm.

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Claim 20 (Original)

An image forming method comprising the step of forming an image by exposing the thermally developable light-sensitive material described in claim 1 with an laser having an wavelength of from 780 nm to 830 nm.